

ABSTRACT OF THE DISCLOSURE

A vacuum apparatus used for a semiconductor manufacturing process or the like is provided, which is space-saving and provided at low cost. A work-piece is transferred to a transfer chamber from the outside under an atmospheric pressure and disposed on a work-piece holder hand inside the transfer chamber, and the transfer chamber is blocked from the outside and the inside of the chamber is made to be in a vacuum. Thereafter, a gate valve provided between the transfer chamber and the process chamber is opened and a pair of tapes made of an elastic material of the transfer apparatus set inside the transfer chamber is extended to the inside of the process chamber. The work-piece disposed on the work-piece holder hand, which is provided in the tip end portion of the tape, is set in the process chamber, or the work-piece having finished processing is disposed on the work-piece holder hand, thereby returning the object to the transfer chamber by returning the tape.

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